

Analysis of the Optical Near-Field due to PbTe Thin Films for Super-resolution Optical Memory

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- ✓ Introduction

- Optical memory
- Super resolution

- ✓ Research motive

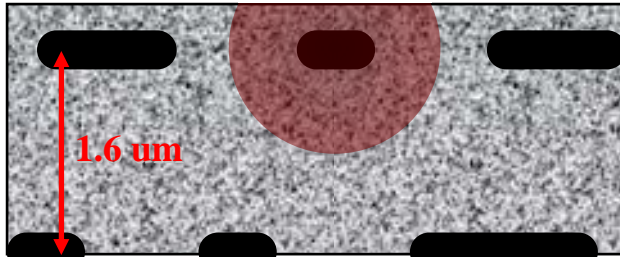
- ✓ Experiment and Results

- Near-field measurement of PbTe films
: experimental set-up & results
- Computation analysis

- ✓ Conclusion & Summary

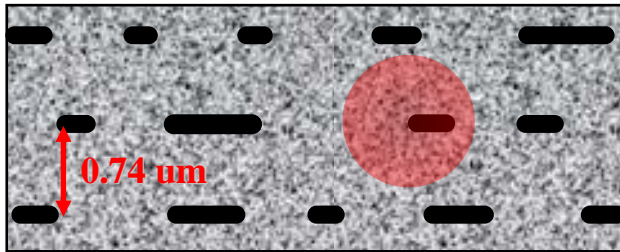
CD

- ✓ 0.65 GB
- ✓ NA 0.45
- ✓ $\lambda = 780\text{nm}$



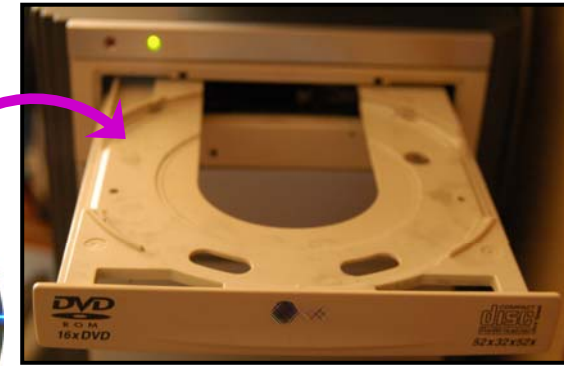
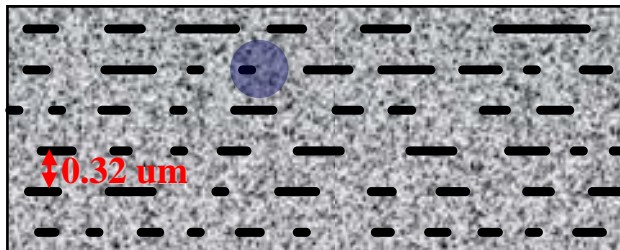
DVD

- ✓ 4.7 GB
- ✓ NA 0.6
- ✓ $\lambda = 650\text{nm}$



Blu-ray

- ✓ 25 GB
- ✓ NA 0.85
- ✓ $\lambda = 405\text{nm}$



$$\text{Density} \propto \frac{NA}{\lambda}$$

- ✓ High density

→ Small pits & resolution

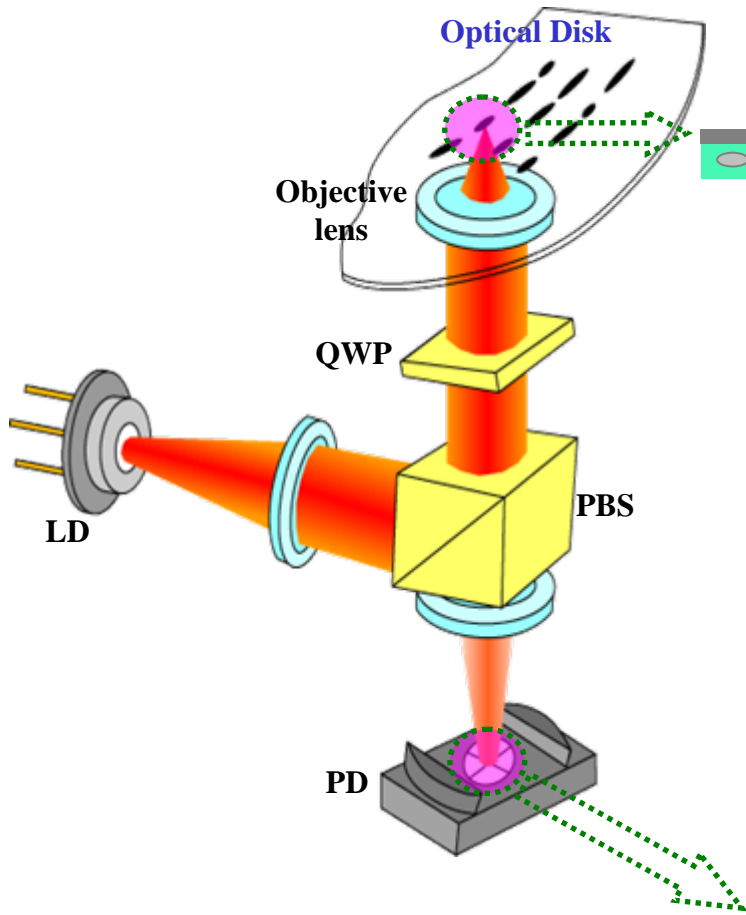
→ Optical diffraction resolution limit

(λ / NA : wavelength / lens NA)

- ✓ Removability

⇒ Super resolution

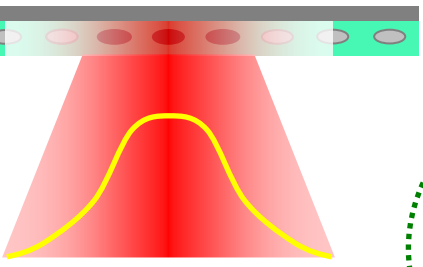
Diffraction limit NA : 1, Visible wavelength : 400 ~ 700 nm



Laser beam spot

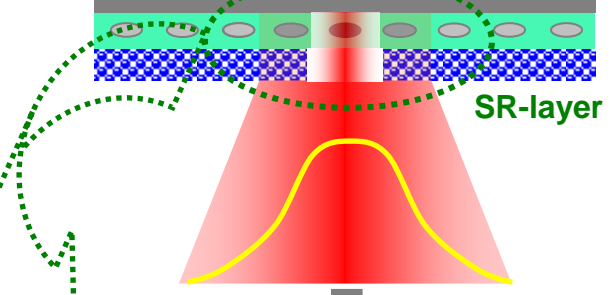
$$\lambda / NA$$

W/O SR-layer



Spot > 2 x period

With SR-layer

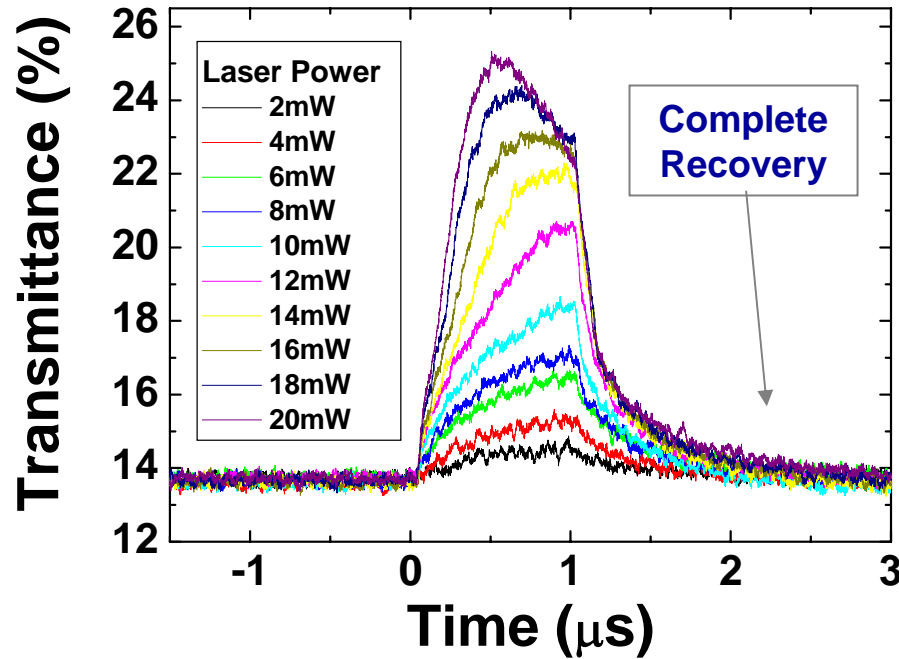


- ✓ Active Aperture
- ✓ Near-field coupling with pits



Spot < 2 x period

● Optical Nonlinearity of PbTe



Far-field averaged intensity

✓ Active aperturing
 ⇒ Near-field intensity profile measurement



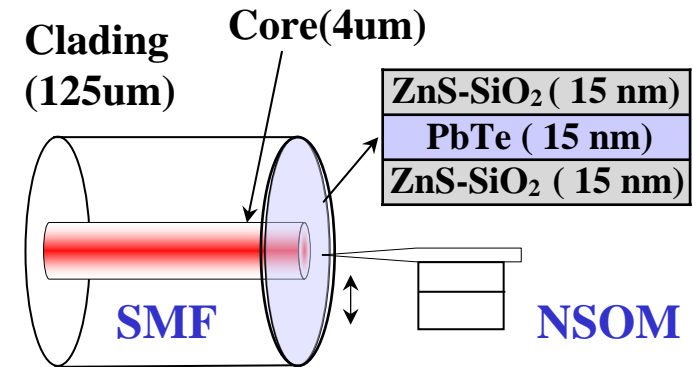
✓ SR mechanism
 ⇒ Computation analysis

- ✓ Fast & large optical response.
- ✓ Complete recovery after laser beam off.

- H.S. Lee, et al, *Appl. Phys. Lett.*, 85, 2782 (2004)
- H.S. Lee, et al, *Surface & Coatings Tech.* 193(2005) 335
- T.S. Lee, et al, *J. Nanosci. Nanotechnol.*(2006) ; to be published

● Sample preparation

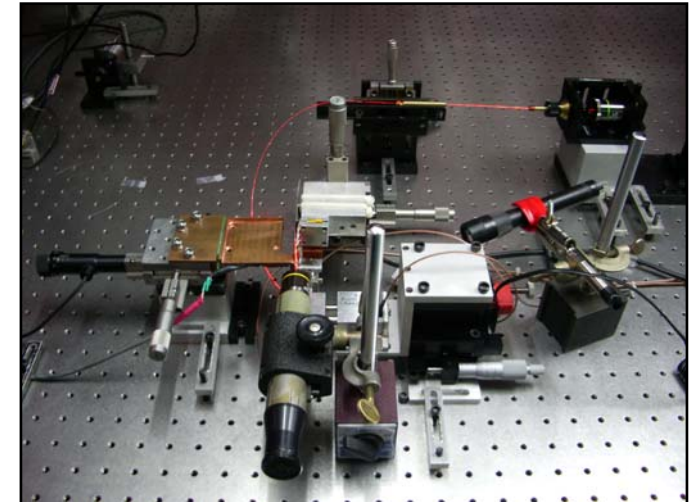
- Substrate : Cleaved facet single mode fiber
- Stack : ZnS-SiO₂ / PbTe / ZnS-SiO₂
- ZnS-SiO₂ : prevent oxidation of PbTe film
- RF magnetron sputtering method



- ✓ No alignment of the sample
- ✓ No spatial filtering of the input beam
- ✓ Fixed beam size

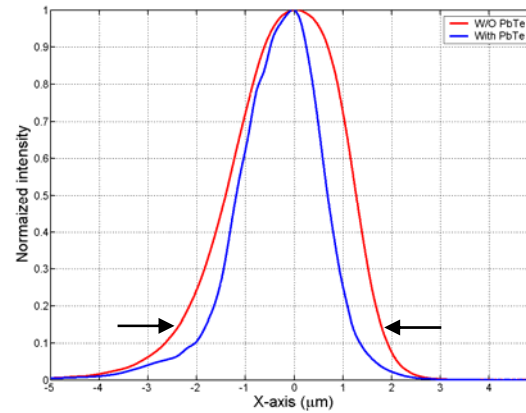
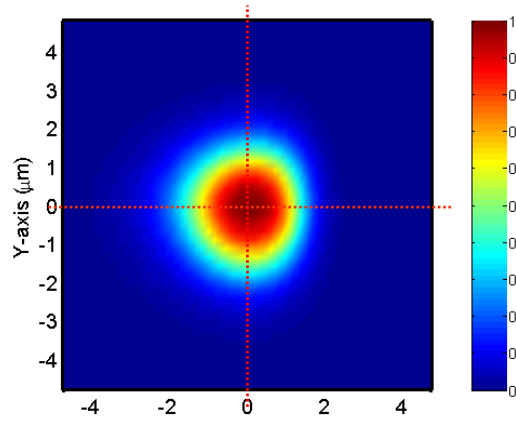
● Measurement instrument

- Lab-made active feedback NSOM
- Tip aperture diameter : 100 nm
- Tip aperture coating : Al
- Tip - sample distance : < 20 nm
- Input beam : 632.8nm He-Ne laser(25mW)



➤ *K.B. Song, et al, S.H. Park, Appl. Phys. Lett., p2260 (1998)*

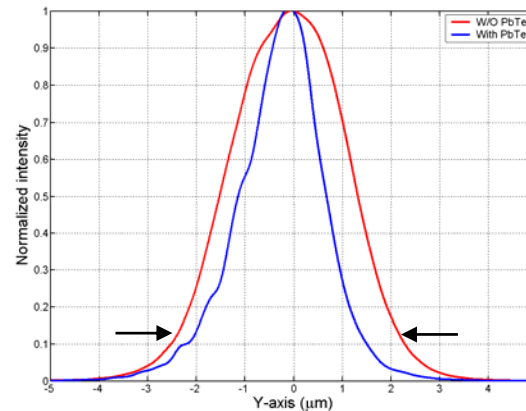
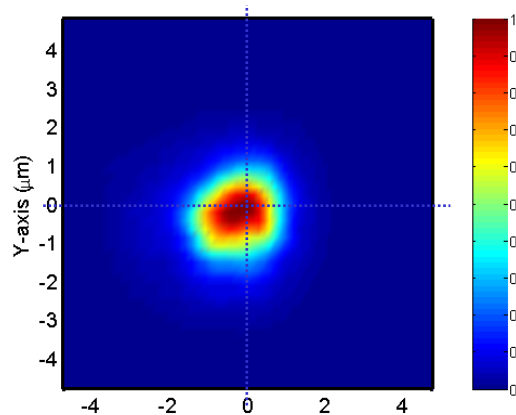
Bare fiber



1/e² size

- ✓ Bare fiber : 4.25 μm
- ✓ With PbTe : 3.08 μm

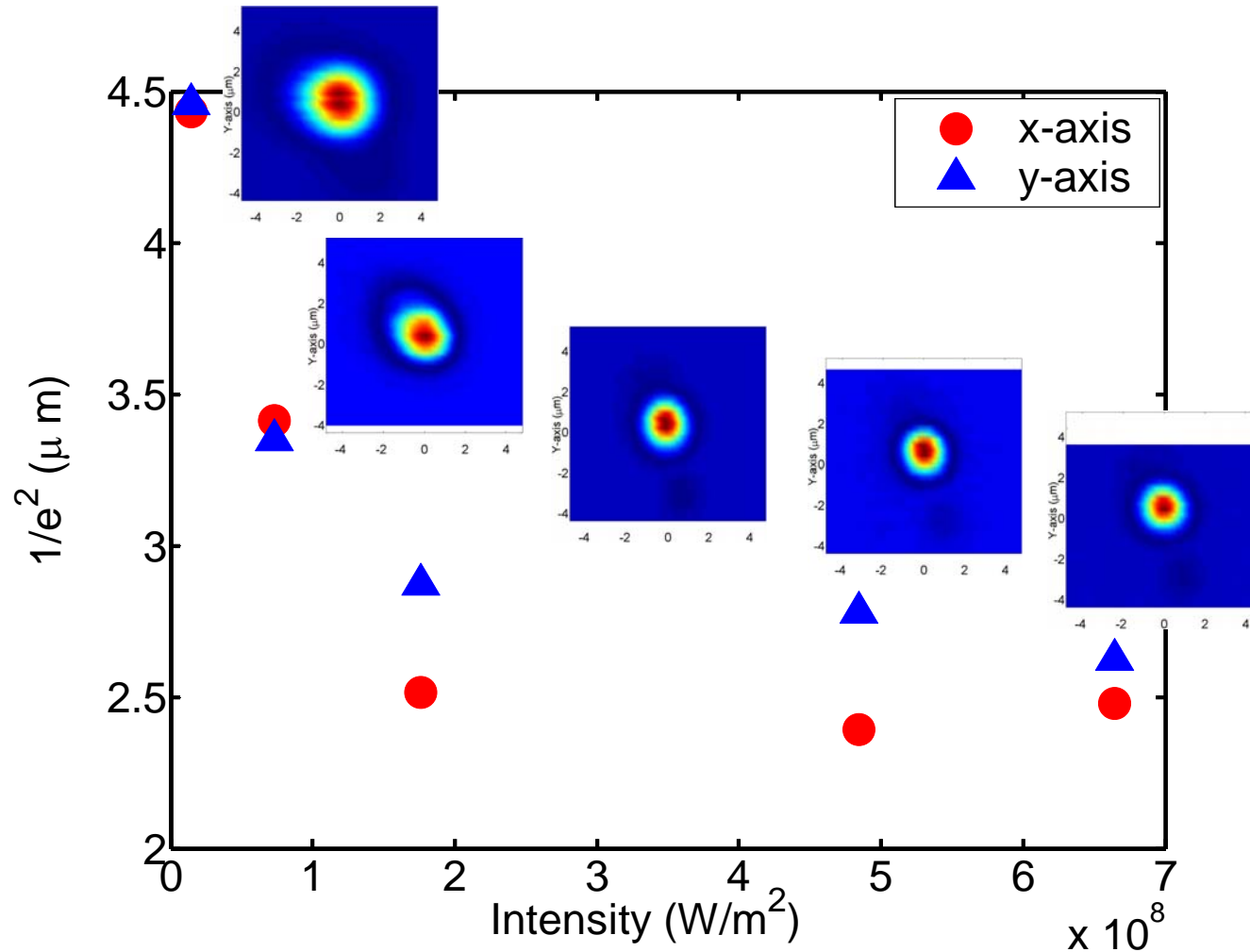
With PbTe layer



1/e² size

- ✓ Bare fiber : 4.49 μm
- ✓ With PbTe : 3.35 μm

⇒ Spot size was reduced in near-field region with the PbTe thin film !



⇒ Spot size reduction at the PbTe thin films in the near-field region is due to the intensity dependent optical nonlinear effect !

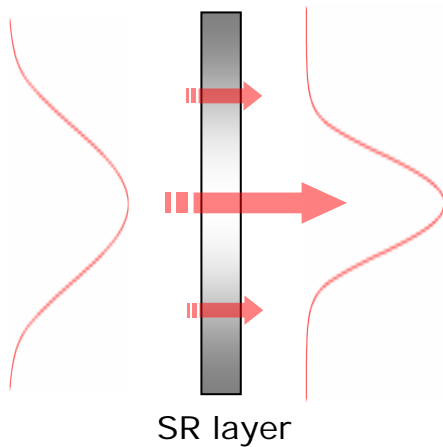
● Finite Difference Time Domain (FDTD)

- ✓ Maxwell's eq. in differential form
 - ✓ Without approximation
- } Full vector diffraction calculation method

$$\frac{\partial \vec{E}}{\partial t} = \frac{1}{\varepsilon} (\nabla \times \vec{H} - \sigma \vec{E}) \Rightarrow \begin{cases} \frac{\partial E_x}{\partial t} = \frac{1}{\varepsilon} \left[\frac{\partial H_z}{\partial y} - \frac{\partial H_y}{\partial z} - \sigma E_x \right] \\ \frac{\partial E_y}{\partial t} = \frac{1}{\varepsilon} \left[\frac{\partial H_x}{\partial z} - \frac{\partial H_z}{\partial x} - \sigma E_y \right] \\ \frac{\partial E_z}{\partial t} = \frac{1}{\varepsilon} \left[\frac{\partial H_y}{\partial x} - \frac{\partial H_x}{\partial y} - \sigma E_z \right] \end{cases}$$

$$\begin{aligned} & \frac{E_x|_{i,j+\frac{1}{2},k+\frac{1}{2}}^{n+\frac{1}{2}} - E_x|_{i,j+\frac{1}{2},k+\frac{1}{2}}^{n-\frac{1}{2}}}{\Delta t} \\ &= \frac{1}{\varepsilon} \left[\frac{H_z|_{i,j+1,k+\frac{1}{2}}^n - H_z|_{i,j,k+\frac{1}{2}}^n}{\Delta y} - \frac{H_y|_{i,j+\frac{1}{2},k+1}^n - H_y|_{i,j+\frac{1}{2},k}^n}{\Delta z} \right. \\ & \quad \left. - \sigma \frac{E_x|_{i,j+\frac{1}{2},k+\frac{1}{2}}^{n+\frac{1}{2}} + E_x|_{i,j+\frac{1}{2},k+\frac{1}{2}}^{n-\frac{1}{2}}}{2} \right] \end{aligned}$$

● Nonlinear optical properties in SR layer



$$n(\vec{r}) = n_0 + n_2 |\vec{E}(\vec{r})|^2$$

$$\kappa(\vec{r}) = \kappa_0 + \kappa_2 |\vec{E}(\vec{r})|^2$$

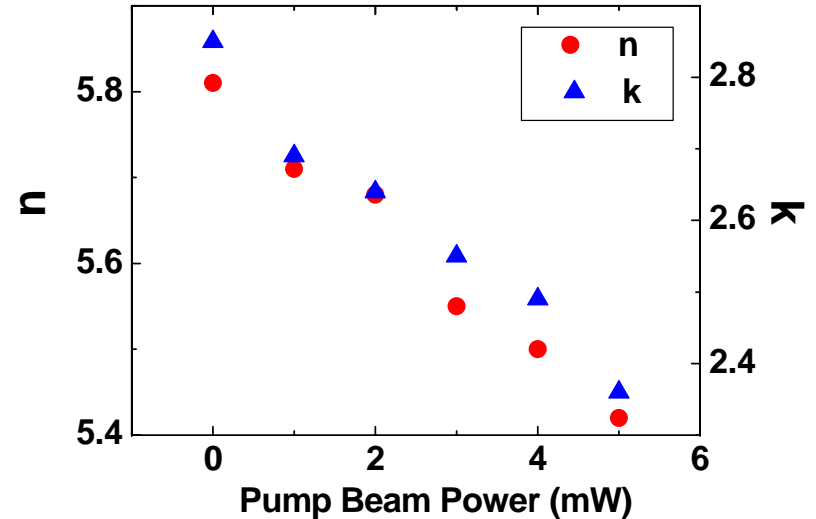
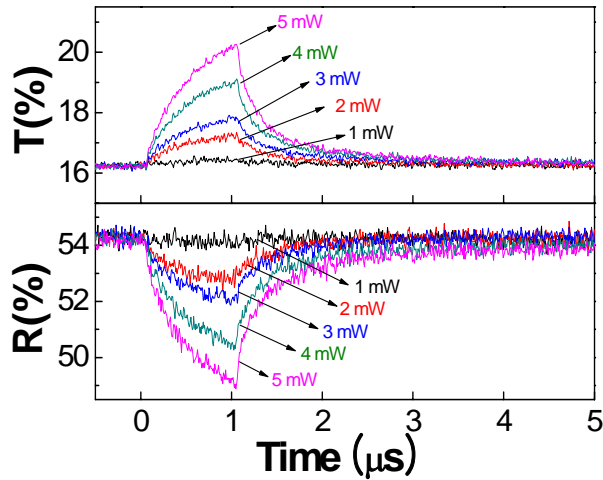


$$[\hat{n}(\omega)]^2 = [n(\omega) + i\kappa(\omega)]^2 = \frac{c^2}{\omega^2} k^2$$

$$= \varepsilon + i \frac{\sigma}{\varepsilon_0 \omega}$$

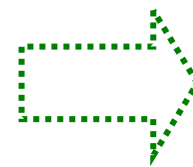
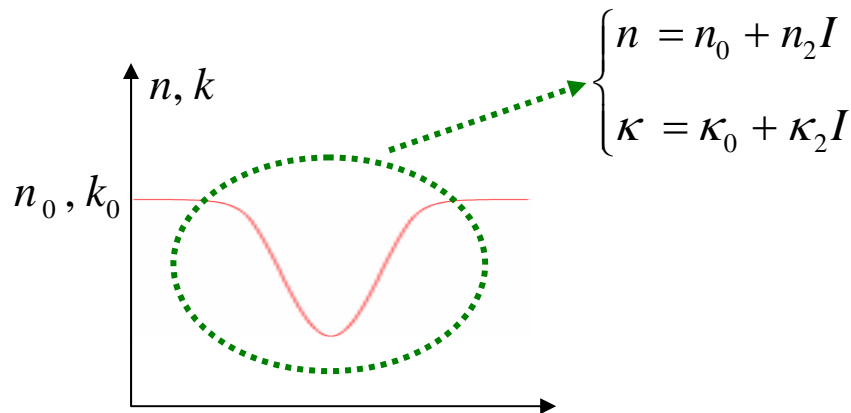
➤ Insideoptics™, RayWiz-FDTD

● Far-field real-time R/T results



➤ T.S. Lee, et al. *J. Nanosci. Nanotechnol.*(2006) ; to be published

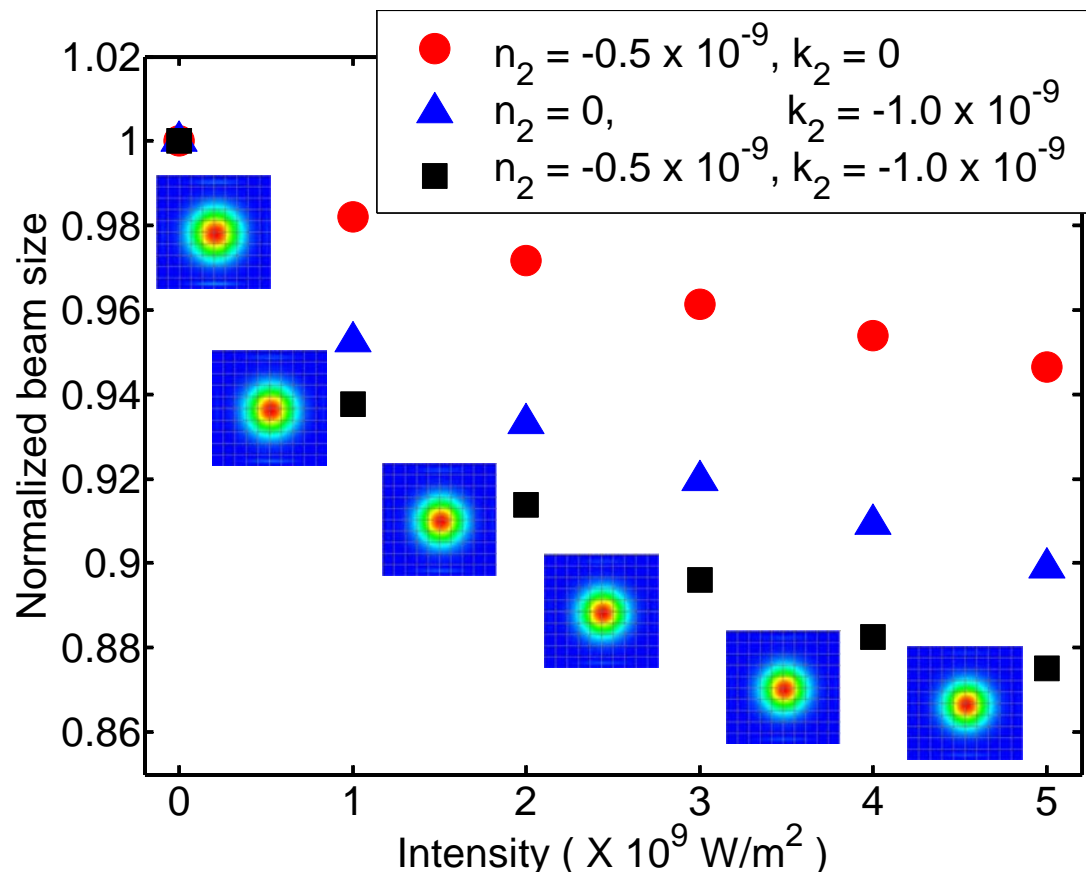
● Nonlinear optical parameter for calculation



$$n = 5.8 - 0.5 \times 10^{-9} I$$

$$\kappa = 2.9 - 1.0 \times 10^{-9} I$$

$$I = 1.0 \times 10^9 \text{ W/m}^2$$



$$n = n_0 + n_2 I$$

$$\kappa = \kappa_0 + \kappa_2 I$$

$$I = 1.0 \times 10^9 \text{ W / m}^2$$

➤ Insideoptics™, RayWiz-FDTD

- ⇒ Nonlinear optical properties affect the reduction of the spot size !
- ⇒ When the laser beam illuminate to the PbTe thin film, saturable absorption due to reduction k and reduction in refractive index are derived !

- ✓ Near-field intensity profile of PbTe thin films are measured with NSOM.
- ✓ From the experimental result, it was found that spot size in the vicinity of PbTe material was reduced with no abrupt beam profile change.
- ✓ In the computational analysis, a phenomenological nonlinear optical model is developed within the framework of a FDTD method.
- ✓ Simulation results shows that optical properties of the PbTe thin film depend on the input laser intensity, and the reduction of the spot size in the near-field region is due to refractive index and extinction coefficient both.

Thank you very much for your kind attention.